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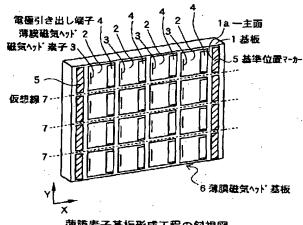
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(54) 【発明の名称】 複合型磁気ヘッドの製造方法

(57) 【要約】

【課題】 組み立て時の組立精度と強度の向上を図るこ とができる複合型磁気ヘッドの製造方法を提供する。

【解決手段】 対向保護板11を一方側面側11aを残 して他方側面側11 bが断面略々凹状となる電極引き出 し端子の露出溝13を連続して形成し、接着ブロック1 0を各チップに切断するに際して、各凹状の露出溝13 の後方の開口垂線側から切断する。



薄膜素子基板形成工程の斜視図

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【特許請求の範囲】

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【請求項1】 電極引き出し端子を有する薄膜ヘッド素子が磁気記録媒体摺動面と直交する方向に複数配列形成されてなる薄膜磁気ヘッド基板を形成する工程と、

上記薄膜磁気ヘッド基板に対向して配される対向保護基板をその一方側面側を残して他方側面側が凹状の開口とされる櫛歯状に形成する工程と、

上記薄膜磁気ヘッド基板に上記対向保護基板を接合する 工程と、

上記対向保護基板が接合された薄膜磁気ヘッド基板を切 10 断して、各磁気ヘッド部に分離する工程と、

複数の磁気ヘッド部を磁気記録媒体走行方向に配列し、 接合一体化する工程と、 を有することを特徴とする複 合型磁気ヘッドの製造方法。

【発明の詳細な説明】

[0001]

【発明の属する技術分野】本発明は、例えばコンピュータ用データカートリッジ等の高密度記録可能な磁気記録 再生装置に搭載して好適な複合型磁気ヘッドの製造方法 に関する。

[0002]

【従来の技術】高密度磁気記録に適した薄膜磁気ヘッドは、より高容量化へと移行しつつあるコンピュータ用のテープストリーマーなどの分野において、バルクタイプの磁気ヘッドに代わり採用化が進められている。

【0003】特に近年は、より高密度化への対応により、記録用ヘッドとしてインダクティブヘッドを使用し、再生用ヘッドとして磁気記録媒体からの信号磁界を電気抵抗変化に変換し検出する磁気抵抗効果型磁気ヘッド(以下、MRヘッドと称する。)が用いられている。【0004】この薄膜磁気ヘッドは、一般に、電極引き出し端子を有する薄膜ヘッド素子が複数形成された素子基板と、この素子基板に対向して配される対向保護板と、上記素子基板の磁気記録媒体との摺動部を補う並列保護板を備えた構成となされている。

【0005】上記素子基板及び対向保護板は、薄膜ヘッド素子よりも該薄膜ヘッド素子のトラック幅方向において幅広となされ、磁気記録媒体との当たり特性を確保している。また、対向保護板は、薄膜ヘッド素子を保護するものであり、電極引き出し端子の位置に対応する位置 40にワイヤボンディング又は半田接続等のための露出溝が一側面に広く形成されている。

【0006】このような薄膜磁気ヘッドは、その必要に応じて、インダクティブヘッドを有する薄膜磁気ヘッド とMRヘッドを有する薄膜磁気ヘッド等といった組み合わせで複数の薄膜磁気ヘッドが接着され複合型磁気ヘッドとされて使用に供される。

【0007】ところで、このような複合型磁気ヘッドを 構成する薄膜磁気ヘッド (MRヘッドを含む)を製造す るに際しては、半導体集積回路と同様に、磁気回路部を 50 構成する磁気薄膜や導体コイル等が蒸着、スパッタリング等の真空薄膜形成技術や写真製版、エッチング等の手法を用いて作成されるため、一般的には3~5インチ程度の基板サイズで作成されることが多い。

【0008】ここで、半導体集積回路の場合と同様に、 薄膜形成過程における1ヘッド当たりに要する工程数を 減らし、且つ1ヘッド当たりの歩留まりを稼ぎコストダ ウンを図る目的で、できるだけ基板サイズを大きくする 一方、個々の薄膜ヘッド素子の形成に要する基板上の占 有面積を必要最小限に小さくし、同一面積の素子基板1 枚当たりから取れるヘッドの数ができるだけ多くなるよ うにする必要がある。

【0009】ところが、薄膜ヘッド素子よりも幅の広い磁気記録媒体との摺動部を必要とする薄膜磁気ヘッド、例えばコンピュータ用テープストリーマーに用いられる薄膜磁気ヘッド等においては、薄膜ヘッド素子のない余白部分の占める面積が多くなるため、一枚の素子基板内に入れられるヘッドの数を多くすることができなくなってしまう。このような薄膜磁気ヘッドでは、薄膜形成工程が数十工程以上と全体の工程数中での占める割合が非常に多いことから、特に歩留まりの観点から結果的にはコストアップを招くことが多い。

【0010】従来、かかる薄膜磁気ヘッドにおいては、 上述の問題を回避するために、1ヘッド分の幅寸法を薄膜ヘッド素子の形成された素子基板のトラック幅方向の 両端面に必要とする磁気記録媒体との摺動幅を補う並列 保護板と上記薄膜ヘッド素子を保護する対向保護板とを 後の工程で接着する方法を採っている。

【0011】即ち、上記薄膜磁気ヘッドは、以下のよう30 な製造方法により製造されている。

【0012】先ず、例えば図10に示すように、先ず蒸着、スパッタリング、或いはエッチング等の薄膜形成技術を用いて薄膜磁気ヘッド31を基板30の表面にマトリクス状に形成し、薄膜磁気ヘッド基板34を作製する。この薄膜磁気ヘッド31には、薄膜ヘッド素子32と、該薄膜ヘッド素子32からの電極引き出し端子33とが形成されている。

【0013】次に、上記薄膜磁気ヘッド基板34を図10中点線で示す仮想線35に沿って切断し、図11に示すような切断プロック36を作製する。

【0014】次いで、図12に示すように、切断プロック36を対向保護板37及び並列保護板38と組み合わせ、樹脂或いはガラス等で接着する。これにより、図13に示すような接着プロック39が作製される。

【0015】ここで、対向保護基板37は、薄膜磁気へッド31の薄膜ヘッド素子32を保護するもので、図12に示すように、切断プロック36との接着側に断面略々コ字状の露出溝37aが一定間隔をおいて複数形成されている。この露出溝37aは、薄膜磁気ヘッド基板34の電極引き出し端子33の位置に対応した位置に対向

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保護基板37の両側面を貫通する溝として形成される。 【0016】次に、図13に示すように、仮想線42と 仮想線43に沿って切断する。すなわち、先ず、砥石4 0で仮想線42に沿って切断して1チップに切り出し、 次に、電極引き出し端子33を露出させるために、砥石 41で仮想線43に沿って切断する。

【0017】このように切断すると、図14に示すように、電極引き出し端子33を露出させる露出溝37aが大きく形成された切断チップ44が作製される。

【0018】その後は、磁気記録媒体摺動面Sを、薄膜 10 磁気ヘッド基板34内に設けられたギャップ深さ研磨量を寸法で読みとるマーカー(以下、デプスマーカーと称する。)や電気抵抗の変化で検出する研磨モニター(以下、デプスモニターと称する。)等を用いて、予め定められたギャップ深さ寸法になるように制御して研磨し、図15に示すような研削チップ45を作製する。

【0019】次いで、図16に示すように、研削チップ45の電極引き出し端子33より印刷配線基板46ヘワイヤーボンディング又は半田接続などを用いて電極配線を取り出し、ヘッドチップ47が作製される。

【0020】次に、図17に示すように、上述のように 形成されるヘッドチップ47のうち、記録用磁気ヘッド 素子が形成された記録用磁気ヘッドチップ48と、再生 用磁気ヘッド素子が形成された一対の再生用磁気ヘッド チップ49と、消去用磁気ヘッド素子が形成された消去 用磁気ヘッドチップ50と、テープガイド51とを組み 合わせて、パーマロイなどから成るシールド枠52内に 位置決めし、樹脂などで固定する。これにより、複合型 磁気ヘッド53が作製される。

[0021]

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【発明が解決しようとする課題】ところで、記録用磁気 ヘッドチップ48と、一対の再生用磁気ヘッドチップ4 9とは、接合一体化された複合型磁気ヘッド53として 使用に供されるが、上記従来の複合型磁気ヘッド53で は、以下に示すような不都合が生じる。

【0022】すなわち、図17に示す複合型磁気ヘッド53を作製する場合、ヘッドチップ同士を組み合わせて各種位置調整を行う。その中で図18に示すチルト調整を行う際には、通常は、各ヘッドチップ48,49の切断チップ、対向保護板37及び並列保護板38の厚み精40度が得られているので、各ヘッドチップ48,49同士を側面基準板57に当接し加圧することで調整する。しかしながら、このとき、各ヘッドチップ48,49の対向保護板の高さ寸法H2が切断チップ及び並列保護板の高さ寸法H1に比べ、薄膜ヘッド素子の電極引き出し端子33を露出させる寸法分だけ短いため、当接し加圧する時、扇状に開き易く調整する上での安定性に問題があった。

【0023】また、各ヘッドチップ48,49は、対向 されているために、隣接する磁気へ保護基板37の後端側がすべて除去され、薄膜磁気ヘッ 50 きくなり、組立状態が安定化する。

ド基板34と対向保護基板37とは、露出溝37aの上方側でのみ接着されている。したがって、対向保護基板37は、従来の製造方法により接合一体化しても、隣接する薄膜磁気ヘッドとの接着側37bの面積が小さいために、ヘッドチップ同士の接着面にズレが生じやすかった。このようなズレが生じると、各ヘッドチップ間での垂直度が正確に保たれず、磁気記録媒体との当たりにばらつきを生じさせる原因となる。

【0024】さらに、従来の製造方法では、図13に示すように、接着ブロック39を砥石40で仮想線42に沿って切断する場合、あらかじめ薄膜磁気ヘッドに形成された切断基準位置マーカーが対向保護板37に隠れているため、切断基準位置マーカー確認用溝入れをして接着ブロック39をアライメントしなおさなければならない。さらには、砥石41で仮想線43に沿って電極引き出し端子33を露出させるための切断も行わなければならないため、加工工程が多くなり、加工効率が悪くなっている。

【0025】そこで、本発明は、かかる従来の技術的な 20 課題に鑑みて提案されたものであって、組み立て時の組 立精度と強度の向上が図られる複合型磁気ヘッドを加工 工程数を最小限度に抑えて効率良く製造することができ る複合型磁気ヘッドの製造方法を提供することを課題と する。

[0026]

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【課題を解決するための手段】本発明の複合型磁気へッドは、上記の課題を解決するために、電極引き出し端子を有する薄膜へッド素子が磁気記録媒体摺動面と直交する方向に複数配列形成されてなる薄膜磁気へッド基板を形成する工程と、上記薄膜磁気へッド基板に対向して配される対向保護基板をその一方側面側を残して他方側面側が凹状の開口とされる櫛歯状に形成する工程と、上記対向保護基板が接合された薄膜磁気へッド基板を切断して、各磁気へッド部に分離する工程と、複数の磁気へッド部を磁気記録媒体走行方向に配列し、接合一体化する工程とを有することを特徴とする。

【0027】本発明によれば、対向保護板をその一方側面側を残して他方側面側が凹状の開口とされる櫛歯状に形成するために、従来のように1チップに切り出した後に、更に、電極引き出し端子を露出させるための切断が不要となる。

【0028】そして、対向保護基板が接合された薄膜磁気へッド基板を切断すると、電極引き出し端子上が解放されるとともに、各切断チップは対向保護板の一方側面部を残して切断される。したがって、このように製造された薄膜磁気へッドを有する複合型薄膜磁気へッドを組み合わせて作製する場合、対向保護板の一方側面部が残されているために、隣接する磁気ヘッド部側の面積が大きくなり、組立状態が安定化する。

[0029]

【発明の実施の形態】以下、本発明を適用した具体的な 実施の形態について図面を参照しながら詳細に説明す

【0030】本実施の形態は、記録用ヘッドを有する薄 膜磁気ヘッドと、再生用ヘッドを有する薄膜磁気ヘッド と、消去用ヘッドを有する薄膜磁気ヘッドを接着した複 合型の薄膜磁気ヘッドの製造方法に、本発明を適用した 例について述べる。

【0031】本実施の形態の複合型磁気ヘッドの製造方 10 法においては、先ず図1に示すように、基板1の一主面 1 a に蒸着、スパッタリング或いはエッチング等の薄膜 形成技術を用いて薄膜磁気ヘッド2を、図中矢印Xで示 す磁気記録媒体摺動面と直交する方向と図中矢印Yで示 す上記薄膜磁気ヘッド2のトラック幅方向にマトリクス 状に形成する。

【0032】ここで、上記薄膜磁気ヘッド2には、磁気 ヘッド素子3と該磁気ヘッド素子3からの電極引き出し 端子4が形成されている。

【0033】また同時に、上記基板1のX方向の両端で 20 あって上記薄膜磁気ヘッド2の形成されていない部分 に、該薄膜磁気ヘッド2の形成位置に合わせて図中斜線 部で示す複数の基準位置マーカー5を形成して薄膜磁気 ヘッド基板6を作製する。

【0034】そして、上記薄膜磁気ヘッド基板6を、最 終的に磁気記録媒体(磁気テープ等)と接する摺動面と なる面方向(Y方向)に対して垂直の方向(X方向)を なす図中点線で示す仮想線7に沿って切断する。

【0035】これにより、上記薄膜磁気ヘッド基板6 が、図2に示すように、X方向、即ち上記磁気記録媒体 30 摺動面に直交する方向に複数 (ここでは4つ) の薄膜磁 気ヘッド2が配列形成され、そのX方向の両端に基準位 置マーカー5が形成されている切断ブロック8に分断さ れる。

【0036】次いで、図3に示すように、切断プロック 8と並列保護板9及び櫛歯状に形成された対向保護板1 1を組み合わせ、樹脂或いはガラス等で接着する。これ により、図4に示すような接着ブロック10が作製され る。すなわち、磁気記録媒体との摺動部として機能する 並列保護板9及び対向保護板11との接着により、接着 40 ブロック10は、薄膜磁気ヘッド2のトラック幅方向の 幅が該薄膜磁気ヘッド2よりも幅広の媒体摺動部を有す る構成となる。

【0037】ここで、上記対向保護板11は、その全体 形状が櫛歯状を呈してなる。すなわち、この対向保護板 11は、その一方側面側11aを残して、他方側面側1 1 bに電極引き出し端子4を解放する凹状の開口13が 形成されている。したがって、切断ブロック8と対向保 護板11との接着後も切断位置マーカー5と電極引き出

6 め、ワークアライメントをすぐに行うことができる。

【0038】次に、砥石14で図4中仮想線A-Aに沿 って切断して1チップに切り出すことで、図5に示すよ うな切断チップ15が作製される。この切断の際、前述 した基準位置マーカー5を用いて切断する。

【0039】ここで、上記対向保護板11は、一方側面 部11aを残して形成されているために、並列保護板9 の片側に磁気記録媒体摺動面側からバック面側まで同じ 厚みの箇所が形成される。

【0040】この点、従来の製造方法では、電極引き出 し端子上の対向保護基板を除去するために、薄膜形成基 板の電極引き出し端子側から1チップ毎に先ず切断する とともに、その後更に、対向保護基板の後端側すべて除 去という工程を要していた(図13参照)。しかし、こ のような切断工程では、切断工数が多くかかる。このこ とは、薄膜磁気ヘッド基板2に連続して配される薄膜へ ッド素子3の数が増えれば増えるほど顕著になる。

【0041】これに対して、本実施の形態の製造方法 は、上記接着ブロック10を各切断チップ15に切断す るに際して、上記凹状の開口13の後方の開口垂線側か ら切断すれば足り(図4中、A-A線)、従来のように 1チップに切り出した後に、更に、電極引き出し端子4 を露出させるための切断が不要となる。しかも、対向保 護板11の一方側面部11bが残されているために、隣 接する磁気ヘッド側の面積が大きくなり、組立状態を安 定化させることができる。

【0042】その後は、この切断チップ15における磁 気記録媒体摺動面Sを、従来より使用されているデプス マーカーやデプスモニター等を用いて、予め定められた ギャップ深さ寸法になるように制御し複数個の切断チッ プ15を同時に研削ラッピングして、図6に示すような 研削チップ16を作製する。

【0043】この時、上記薄膜磁気ヘッド2のデプス は、数μmの精度で制御する必要がある。そこで、上述 のように基板1上に薄膜磁気ヘッド2を形成すると同時 に上述のデプスマーカーやデプスモニターを形成してお き、これによりデプス方向の研削量を確認しながら切断 チップ15のデプスのバラツキを抑え、且つ全体の加工 工数を抑える。

【0044】次いで、この研削チップ16から薄膜ヘッ ド素子3の電極引き出し端子4より印刷配線基板19へ ワイヤーボンディング又は半田接続などを用いて電極配 線を取り出し、図7に示すようなヘッドチップ1が作製

【0045】次に、図8に示すように、上記ヘッドチッ プ1のうち記録用磁気ヘッド素子が形成された薄膜磁気 ヘッドチップ1Aと、再生用磁気ヘッド素子が形成され た一対の薄膜再生ヘッドチップ1 Bと、消去磁気ヘッド チップ1Cと、テープガイド17などを組み合わせてパ し端子4が、凹状の開口13から露出することになるた 50 ーマロイなどから成るシールド枠18に位置決めし、樹

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示す斜視図である。

脂などで固定する。これにより、複合型磁気ヘッド21 が作製される。

【0046】このようして組み立てられた複合型磁気ヘッド21は、図9に示すように、対向保護板11の一方側面部11aが残されているために、各ヘッドチップ1A、1Bは、並列保護板9と対向保護板11の高さが同じ箇所が設けられる。したがって、側面基準板20に当接し加圧しても、従来のように扇形に開くことはない。また、対向保護板11が櫛歯状に形成されているために、ワイヤーボンディング等の接続作業が改善されると10同時に歩留まりも改善できる。

【0047】さらに、本実施の形態においては、上記構成の対向保護板11に切断ブロック8と並列保護板9を接着するため、ギャップ平行度は問題とならず、複合型磁気ヘッドの製造が容易となる。

【0048】以上、本実施の形態では、磁気ヘッドが3つ組み合わされて構成された複合型磁気ヘッドを用いて説明したが、本発明は、これに限定されるものではないことは言うまでもない。また、本実施の形態では、少なくとも薄膜ヘッド素子と電極引き出し端子を有する薄膜20磁気ヘッド基板とこの薄膜磁気ヘッド基板を保護する対向保護基板とからなる磁気ヘッドを含むものであれば広く適用されるものである。

[0049]

【発明の効果】本発明の複合型磁気ヘッドの製造方法は、櫛歯状に形成された対向保護基板が接合された薄膜磁気ヘッド基板を1チップに切り出すことで、複合型磁気ヘッドを構成することとなる磁気ヘッド部が作製されるために、従来の切断基準位置マーカ確認用溝入れと電極引き出し端子を露出させるための切断が不要となり、加工効率の改善による製造時間の短縮化、生産性の向上、コストダウンが図られる。

【0050】さらに、本発明の複合型磁気ヘッドの製造方法は、対向保護基板が接合された薄膜磁気ヘッド基板を切断すると、電極引き出し端子上が解放されるとともに、各切断チップは対向保護板の一方側面部を残して切断されるために、このように製造された磁気ヘッド部を有する複合型薄膜磁気ヘッドを組み合わせる場合、対向保護板の一方側面部が残されているために、隣接する磁気ヘッド部側の面積が大きくなり、組立状態が安定化す 40ることになる。したがって、複合型磁気ヘッドの組立強度と組立精度の向上が図られるとともに、磁気記録媒体との当たりにばらつきを生じさせることを防止することが可能となる。

【図面の簡単な説明】

【図1】本発明が適用される一実施の形態の複合型磁気 ヘッドの製造工程を示す図であり、基板上に複数の薄膜 ヘッドを形成して薄膜素子基板を形成する工程を示す斜 視図である。

【図2】上記複合型磁気ヘッドの製造工程を示す図であ 50

り、薄膜素子基板を切断して形成される切断プロックを

【図3】上記複合型磁気ヘッドの製造工程を示す図であり、薄膜素子基板、並列保護板、及び対向保護板を接着する状態を示す斜視図である。

【図4】上記複合型磁気ヘッドの製造工程を示す図であり、接着ブロックを各チップに切断する状態を示す斜視図である。

【図5】上記複合型磁気ヘッドの製造工程を示す図であり、接着ブロックを各チップに切断する状態を示す斜視 図である。

【図6】上記複合型磁気ヘッドの製造工程を示す図であり、各チップに磁気記録媒体摺動面を形成して研磨チップを作製した状態を示す斜視図である。

【図7】上記複合型磁気ヘッドの製造工程を示す図であり、研磨チップに印刷配線基板を接続して形成されるヘッドチップを示す斜視図である。

【図8】上記複合型磁気ヘッドの製造工程を示す図であり、薄膜磁気ヘッドチップを有する複合型磁気ヘッドを 組み立てた状態を示す斜視図である。

【図9】複数のヘッドチップが側面基準板に当接し加圧 された状態を示す模式図である。

【図10】従来の複合型磁気ヘッドの製造工程を示す図であり、基板上に複数の薄膜磁気ヘッドを形成して薄膜ヘッド素子基板を形成する工程を示す斜視図である。

【図11】従来の複合型磁気ヘッドの製造工程を示す図であり、薄膜ヘッド素子基板を切断して形成される切断プロックを示す斜視図である。

【図12】従来の複合型磁気ヘッドの製造工程を示す図であり、薄膜ヘッド素子基板、並列保護板、及び対向保護板を接着する状態を示す斜視図である。

【図13】従来の複合型磁気ヘッドの製造工程を示す図であり、接着ブロックを各チップに切断する状態を示す 斜視図である。

【図14】従来の複合型磁気ヘッドの製造工程を示す図であり、接着プロックを各チップに切断した状態を示す 斜視図である。

【図15】従来の複合型磁気ヘッドの製造工程を示す図であり、チップに磁気記録媒体摺動面を形成して研削チップを作製した状態をを示す斜視図である。

【図16】上記複合型磁気ヘッドの製造工程を示す図であり、研削チップに印刷配線基板を接続して形成されるヘッドチップを示す斜視図である。

【図17】上記複合型磁気ヘッドの製造工程を示す図であり、薄膜磁気ヘッドチップを有する複合型磁気ヘッドを組み立てた状態を示す斜視図である。

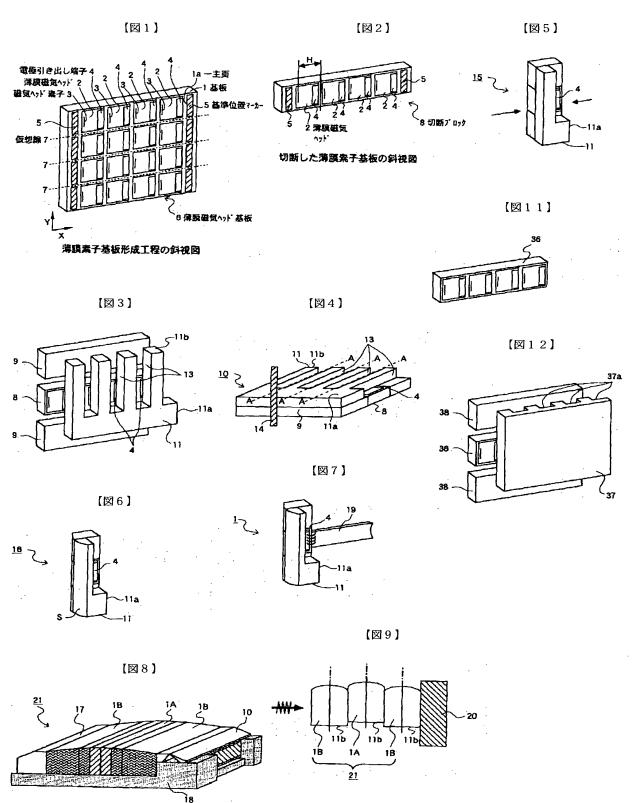
【図18】複数のヘッドチップが側面基準板に当接し加 圧された状態を示す模式図である。

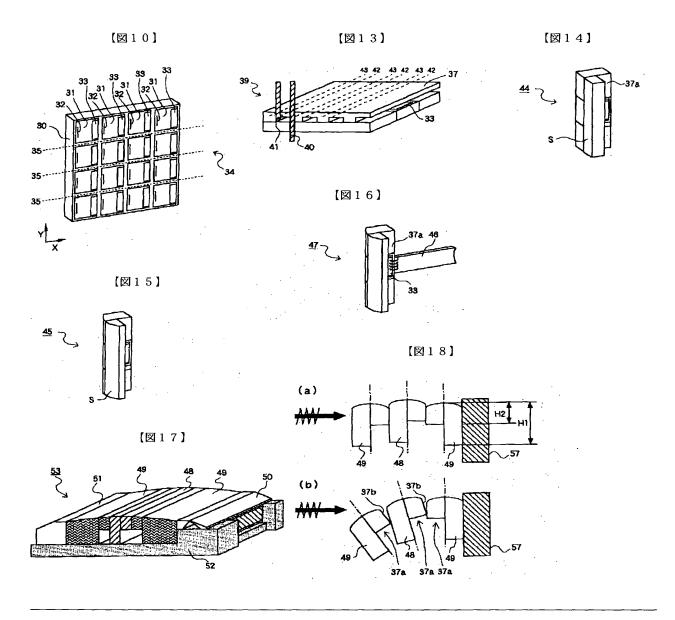
【符号の説明】

1, 1A, 1B, 1C ヘッドチップ、 3 薄膜ヘッ

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ド素子、 4 電極引き出し端子、 1 1 対向保護 板、 1 1 a 対向保護板の一方側面側、 1 1 b 対 向保護板の他方側面側、 13 凹状の開口、 10 接着ブロック、21 複合型磁気ヘッド





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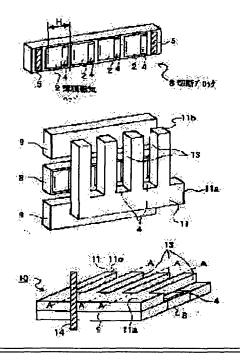
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YAMAZAKI MASAHIKO

(54) MANUFACTURE OF COMPOSITE TYPE MAGNETIC HEAD

PROBLEM TO BE SOLVED: To improve accuracy and strength of assembly to minimize the number of processing steps in order to realize highly efficient manufacture by forming a comb-tooth type protection plate which is provided opposed to a thin film magnetic head substrate with the other side surface being opened leaving one side surface. SOLUTION: With bonding of a parallel protection plate 9 functioning as a sliding section with a magnetic recording medium and an opposing protection plate 11, a bonding block 10 has a medium sliding section in which the width in the track width direction of a thin film magnetic head 2 is wider than the head 2. The opposing protection plate 11 allows formation of a recessed aperture 13 opening an electrode leading terminal 4 toward the other side surface 11b, leaving one side surface 11a. Therefore, even after the bonding of a cutout block 8 and the opposing protection plate 11, since a cutting position marker 5 and electrode leading terminal 4 are exposed from the recessed aperture 13, work alignment can be made immediately.



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of rejection or application converted registration]

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CLAIMS

[Claim(s)]

[Claim 1] The manufacture method of the compound—die magnetic head characterized by providing the following. The process which forms the thin film magnetic—head substrate which comes to carry out two or more array formation in the direction in which a magnetic—recording medium sliding surface and the thin—film—head element which has an electrode drawer terminal cross at right angles. The process which forms the opposite protective—group board which counters the above—mentioned thin film magnetic—head substrate, and is arranged in the shape of [which leaves the one side side / by which an other side side is used as concave opening] a ctenidium. The process which joins the above—mentioned opposite protective—group board to the above—mentioned thin film magnetic—head substrate. The process which cuts the thin film magnetic—head substrate to which the above—mentioned opposite protective—group board was joined, and is divided into each magnetic—head section, and process which arranges two or more magnetic—head sections in the magnetic—recording medium run direction, and carries out junction unification .

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DETAILED DESCRIPTION

[Detailed Description of the Invention]

[0001]

[The technical field to which invention belongs] this invention is carried in the magnetic recorder and reproducing device of for example, the data cartridge for computers etc. recordable high-density, and relates to the manufacture method of the suitable compound-die magnetic head.

[0002]

[Description of the Prior Art] In fields, such as a tape streamer for the computers by which the thin film magnetic head suitable for high-density magnetic recording is shifting to high capacity-ization more, adoption-ization is advanced instead of the bulk type magnetic head. [0003] More, an inductive head is used as a head for record, and the magnetoresistance-effect type magnetic head (an MR head is called hereafter.) which changes the signal magnetic field from a magnetic-recording medium into electric resistance change, and is detected is used as a head for reproduction by the correspondence to densification especially in recent years.

[0004] Generally this thin film magnetic head is made with the composition equipped with the element substrate in which two or more thin-film-head elements which have an electrode drawer terminal were formed, the opposite guard plate which counters this element substrate and is allotted, and the parallel guard plate with which the sliding section with the magnetic-recording medium of the above-mentioned element substrate is compensated.

[0005] In the direction of the width of recording track of this thin-film-head element, the above-mentioned element substrate and the opposite guard plate were made as it is broad, and they have secured the hit property with a magnetic-recording medium from a thin-film-head element. Moreover, an opposite guard plate protects a thin-film-head element, and the exposure slot for wirebonding or solder connection is widely formed in the unilateral side in the position corresponding to the position of an electrode drawer terminal.

[0006] Use is presented with it, two or more thin film magnetic heads in the combination of the thin film magnetic head which has the thin film magnetic head which has an inductive head, and an MR head pasting up if needed [the], and such the thin film magnetic head being used as the compound—die magnetic head.

[0007] by the way, the magnetic thin film which faces manufacturing the thin film magnetic head (an MR head being included) which constitutes such the compound-die magnetic head, and constitutes the magnetic-circuit section like a semiconductor integrated circuit and a conductor — since a coil etc. is created using technique, such as vacuum thin film coating technologies, such as vacuum evaporationo and sputtering, and photoengraving process, etching, generally it is created in many cases in the substrate size of about 3-5 inches

[0008] Occupancy area on the substrate which formation of each thin-film-head element takes while enlarging substrate size as much as possible in order to reduce the number of processes which per 1 in the thin film morphosis head takes like the case of a semiconductor integrated circuit, and to earn the yield per one head and to aim at a cost cut is made small to necessary minimum here, and it is necessary to make it the number of the heads which can be taken from per element substrate of the same area increase as much as possible.

[0009] Since the area which the margin portion which does not have a thin-film-head element in the thin film magnetic head which needs the sliding section with the latus magnetic-recording medium of width of face, for example, the thin film magnetic head used for the tape streamer for computers, rather than a thin-film-head element occupies increases, it will become impossible however, to make [many] the number of heads into which it is put in the element substrate which is. In such the thin film magnetic head, a thin film formation process causes a cost rise from dozens of or more processes and there being very many rates in the inside of the whole number of processes for which it accounts in many cases as a result from a viewpoint of the yield.

[0010] Conventionally, in order to avoid an above-mentioned problem in this thin film magnetic head, the method of pasting up the parallel guard plate with which sliding width of face with the magnetic-recording medium which needs the width-of-face size for one head for the ends side of the direction of the width of recording track of an element substrate in which the thin-film-head element was formed is compensated, and the opposite guard plate which protects the above-mentioned thin-film-head element at a next process is taken.

[0011] That is, the above-mentioned thin film magnetic head is manufactured by the following manufacture methods.

[0012] First, as shown, for example in <u>drawing 10</u>, the thin film magnetic head 31 is first formed in the front face of a substrate 30 in the shape of a matrix using thin film coating technologies, such as vacuum evaporationo, sputtering, or etching, and the thin film magnetic-head substrate 34 is produced. The thin-film-head element 32 and the electrode drawer terminal 33 from this thin-film-head element 32 are formed in this thin film magnetic head 31.

[0013] Next, the above-mentioned thin film magnetic-head substrate 34 is cut along with the imaginary line 35 shown by the <u>drawing 10</u> middle point line, and the cutting block 36 as shown in <u>drawing 11</u> is produced.

[0014] Subsequently, as shown in drawing 12, the cutting block 36 is combined with the opposite guard plate 37 and the parallel guard plate 38, and it pastes up with a resin or glass. Thereby, the adhesion block 39 as shown in drawing 13 is produced.

[0015] Here, cross-section **** KO character-like exposure slot 37a sets a fixed interval, and two or more opposite protective-group boards 37 are formed in the adhesion-with the cutting block 36 side, as the thin-film-head element 32 of the thin film magnetic head 31 is protected and it is shown in drawing 12. This exposure slot 37a is formed in the position corresponding to the position of the electrode drawer terminal 33 of the thin film magnetic-head substrate 34 as a slot which penetrates the both-sides side of the opposite protective-group board 37. [0016] Next, as shown in drawing 13, it cuts along with an imaginary line 42 and an imaginary line 43. That is, in order to cut along with an imaginary line 42 by the grinding stone 40, and to start for one chip first, next to expose the electrode drawer terminal 33, along with an imaginary line 43, it cuts by the grinding stone 41.

[0017] Thus, cutting produces the cutting chip 44 with which exposure slot 37a to which the electrode drawer terminal 33 is exposed was formed greatly, as shown in drawing 14.

[0018] After that, it controls and grinds so that it may become the depth-of-gap size defined beforehand using the polish monitor (a depth

monitor is called hereafter.) which detects the amount of depth-of-gap polishes in which the magnetic-recording medium sliding surface S was formed in the thin film magnetic-head substrate 34 by change of the marker (a depth marker is called hereafter.) and electric resistance which are read with a size, and the grinding chip 45 as shown in <u>drawing 15</u> is produced.

[0019] Subsequently, as shown in drawing 16, electrode wiring is taken out from the electrode drawer terminal 33 of the grinding chip 45 using wire bonding or solder connection to the printed wiring substrate 46, and the head chip 47 is produced.

[0020] Next, as shown in drawing 17, it positions in the shield frame 52 which consists of a permalloy etc. combining the magnetic-head chip 48 for record with which the magnetic-head element for record was formed among the head chips 47 formed as mentioned above, the magnetic-head chip 49 for reproduction of a couple with which the magnetic-head element for reproduction was formed, the magnetic-head chip 50 for elimination with which the magnetic-head element for elimination was formed, and a tape guide 51, and fixes by the resin etc. Thereby, the compound-die magnetic head 53 is produced.

[0021]

[Problem(s) to be Solved by the Invention] By the way, although use is presented with the magnetic-head chip 48 for record, and the magnetic-head chip 49 for reproduction of a couple as the compound-die magnetic head 53 by which junction unification was carried out, in the above-mentioned conventional compound-die magnetic head 53, un-arranging, as shown below produces them.

[0022] That is, when producing the compound-die magnetic head 53 shown in <u>drawing 17</u>, various positioning is performed combining head chips. In case tilt adjustment shown in <u>drawing 18</u> in it is performed, since the thickness precision of the cutting chip of each head chips 48 and 49, the opposite guard plate 37, and the parallel guard plate 38 is acquired, it usually adjusts by pressurizing each head chip 48 and 49 comrades in contact with the side orientation plate 57. However, since the height size H2 of the opposite guard plate of each head chips 48 and 49 is short compared with a cutting chip and the height size H1 of a parallel guard plate by the size to which the electrode drawer terminal 33 of a thin-film-head element is exposed at this time, when contacting and pressurizing, the problem was in stability when it is easy to open to a flabellate and adjusts to it.

[0023] Moreover, all the back end sides of the opposite protective-group board 37 were removed, and each head chips 48 and 49 have pasted up the thin film magnetic-head substrate 34 and the opposite protective-group board 37 only by the upper part side of exposure slot 37a. Therefore, since its area of adhesion side 37b with the adjoining thin film magnetic head is small even if the opposite protective-group board 37 carries out junction unification by the conventional manufacture method, gap tended to produce it in the adhesion side of head chips. If such gap arises, the plumbness during each head chip will not be kept exact, but will become the cause of making the hit by the magnetic-recording medium producing dispersion.

[0024] Furthermore, by the conventional manufacture method, since the cutting criteria position marker beforehand formed in the thin film magnetic head is hidden by the opposite guard plate 37 when cutting the adhesion block 39 along with an imaginary line 42 by the grinding stone 40 as shown in drawing 13, grooving for a cutting criteria position marker check is carried out, and alignment of the adhesion block 39 must be recarried out. Furthermore, in order also to have to perform cutting for exposing the electrode drawer terminal 33 along with an imaginary line 43 by the grinding stone 41, a processing process increases and processing efficiency is bad.

[0025] Then, this invention makes it a technical problem to offer the manufacture method of the compound-die magnetic head that it can be proposed in view of this Prior-art-technical problem, the compound-die magnetic head by which improvement in the assembly precision at the time of an assembly and intensity is achieved can be held down to the minimum, and the number of processing processes can be manufactured efficiently.

[0026]

[Means for Solving the Problem] The process which forms the thin film magnetic-head substrate which comes to carry out two or more array formation in the direction in which a magnetic-recording medium sliding surface and the thin-film-head element which has an electrode drawer terminal cross at right angles in order that the compound-die magnetic head of this invention may solve the above-mentioned technical problem. The process which forms the opposite protective-group board which counters the above-mentioned thin film magnetic-head substrate, and is arranged in the shape of [which leaves the one side side side / by which an other side side is used as concave opening] a ctenidium. The process which joins the above-mentioned opposite protective-group board to the above-mentioned thin film magnetic-head substrate, and the thin film magnetic-head substrate to which the above-mentioned opposite protective-group board was joined are cut. It is characterized by having the process divided into each magnetic-head section, and the process which arranges two or more magnetic-head sections in the magnetic-recording medium run direction, and carries out junction unification.

[0027] In order to form an opposite guard plate in the shape of [which leaves the one side side side / by which an other side side is used as concave opening] a ctenidium according to this invention, after starting for one chip like before, cutting for making it open [begin] becomes unnecessary about an electrode drawer terminal further.

[0028] And if the thin film magnetic-head substrate to which the opposite protective-group board was joined is cut, while an electrode drawer terminal top will be released, each cutting chip leaves the one side lateral portion of an opposite guard plate, and is cut. Therefore, when producing combining the compound-die thin film magnetic head which has the thin film magnetic head manufactured in this way, since [of an opposite guard plate] the lateral portion is left behind on the other hand, the area by the side of the adjoining magnetic-head section becomes large, and an assembly state is stable.

[0029]

[Embodiments of the Invention] It explains in detail, referring to a drawing hereafter about the gestalt of the concrete operation which applied this invention.

[0030] The gestalt of this operation describes the example which applied this invention to the manufacture method of the thin film magnetic head of the compound die which pasted up the thin film magnetic head which has a head for record, the thin film magnetic head which has a head for reproduction, and the thin film magnetic head which has a head for elimination.

[0031] In the manufacture method of the compound-die magnetic head of the gestalt this operation, as first shown in <u>drawing 1</u>, it forms in the direction of the width of recording track of the above-mentioned thin film magnetic head 2 shown by the direction which intersects perpendicularly with the magnetic-recording medium sliding surface which uses thin film coating technologies, such as vacuum evaporationo, sputtering, or etching, for 1 principal-plane 1a of a substrate 1, and shows the thin film magnetic head 2 by the arrow X in drawing, and the arrow Y in drawing in the shape of a matrix.

[0032] Here, the electrode drawer terminal 4 from the magnetic-head element 3 and this magnetic-head element 3 is formed in the above-mentioned thin film magnetic head 2.

[0033] Moreover, two or more criteria position markers 5 shown in the slash section in drawing according to the formation position of this thin film magnetic head 2 are formed in the portion in which it is the ends of the direction of X of the above-mentioned substrate 1, and the above-mentioned thin film magnetic head 2 is not formed simultaneously, and the thin film magnetic-head substrate 6 is produced into it.

[0034] And it cuts along with the imaginary line 7 shown by the drawing middle point line which makes a perpendicular direction (the direction of X) to the direction of a field (the direction of Y) which serves as a sliding surface which finally touches magnetic-recording media (magnetic

tape etc.) in the above-mentioned thin film magnetic-head substrate 6.

[0035] Thereby, as shown in <u>drawing 2</u>, array formation of the thin film magnetic head 2 of plurality (here four) is carried out in the direction of X, i.e., the direction which intersects perpendicularly with the above-mentioned magnetic-recording medium sliding surface, and the above-mentioned thin film magnetic-head substrate 6 is divided by the cutting block 8 with which the criteria position marker 5 is formed in the ends of the direction of X.

[0036] Subsequently, as shown in <u>drawing 3</u>, the opposite guard plate 11 formed the cutting block 8, the parallel guard plate 9, and in the shape of a ctenidium is combined, and it pastes up with a resin or glass. Thereby, the adhesion block 10 as shown in <u>drawing 4</u> is produced. That is, the adhesion block 10 serves as the composition of having the medium sliding section with the width of face of the direction of the width of recording track of the thin film magnetic head 2 broader than this thin film magnetic head 2, by adhesion with the parallel guard plate 9 and the opposite guard plate 11 which function as the sliding section with a magnetic-recording medium.

[0037] As for the above-mentioned opposite guard plate 11, the whole configuration comes to present the shape of a ctenidium here. That is, this opposite guard plate 11 leaves one side side 11a, and the concave opening 13 which releases the electrode drawer terminal 4 to other side side side 11b is formed. Therefore, since the cutting position marker 5 and the electrode drawer terminal 4 will expose after adhesion with the cutting block 8 and the opposite guard plate 11 from the concave opening 13, work alignment can be performed immediately.

[0038] Next, the cutting chip 15 as shown in <u>drawing 5</u> is produced by cutting along with imaginary line A-A in <u>drawing 4</u> by the grinding stone 14, and starting for one chip. It cuts using the criteria position marker 5 mentioned above in the case of this cutting.

[0039] Here, since the above-mentioned opposite guard plate 11, on the other hand, leaves lateral portion 11a and is formed, the part of the same thickness is formed in a back side side from a magnetic-recording medium sliding-surface side at one side of the parallel guard plate 9. [0040] This point and the conventional manufacture method had taken the process of removal altogether the back end side of an opposite protective-group board further after that, while cutting from the electrode drawer terminal side of a thin film formation substrate first for every chip, in order to remove the opposite protective-group board on an electrode drawer terminal (refer to drawing 13). However, at such a cutting process, a cutting man day cuts in many. This becomes more remarkable, as the number of the thin-film-head elements 3 which follow the thin film magnetic-head substrate 2, and are allotted increases.

[0041] On the other hand, after facing the manufacture method of the gestalt this operation cutting the above-mentioned adhesion block 10 for each cutting chip 15, being sufficient for it if it cuts from the opening perpendicular side behind the above-mentioned concave opening 13 (the inside of <u>drawing 4</u>, A-A line), and starting it for one chip like before, it becomes unnecessary further cutting it for exposing the electrode drawer terminal 4. And since [of the opposite guard plate 11] lateral portion 11b is left behind on the other hand, the area by the side of the adjoining magnetic head can become large, and an assembly state can be stabilized.

[0042] After that, the magnetic-recording medium sliding surface S in this cutting chip 15 is controlled to become the depth-of-gap size defined beforehand using a depth marker, a depth monitor, etc. which are used conventionally, grinding wrapping of two or more cutting chips 15 is carried out simultaneously, and the grinding chip 16 as shown in drawing 6 is produced.

[0043] It is necessary to control the depth of the above-mentioned thin film magnetic head 2 by precision of several micrometers at this time. Then, while an above-mentioned depth marker and an above-mentioned depth monitor are formed and this checks the amount of grinding of the direction of a depth at the same time it forms the thin film magnetic head 2 on a substrate 1 as mentioned above, the variation in the depth of the cutting chip 15 is suppressed, and the whole processing man day is stopped.

[0044] Subsequently, electrode wiring is taken out from this grinding chip 16 from the electrode drawer terminal 4 of the thin-film-head element 3 using wire bonding or solder connection to the printed wiring substrate 19, and the head chip 1 as shown in <u>drawing 7</u> is produced. [0045] Next, as shown in <u>drawing 8</u>, it positions in thin film magnetic-head chip 1A in which the magnetic-head element for record was formed among the above-mentioned head chips 1, thin film reproducing-head chip 1B of the couple in which the magnetic-head element for reproduction was formed, elimination magnetic-head chip 1C, and the shield frame 18 that consists of a permalloy etc. combining a tape guide 17 etc., and fixes by the resin etc. Thereby, the compound-die magnetic head 21 is produced.

[0046] As the compound-die magnetic head 21 assembled by carrying out such is shown in <u>drawing 9</u>, since [of the opposite guard plate 11] lateral portion 11a is left behind on the other hand, as for each head chips 1A and 1B, the part where the height of the parallel guard plate 9 and the opposite guard plate 11 is the same is established. Therefore, even if it pressurizes in contact with the side orientation plate 20, it does not open to a sector like before. Moreover, the yield is also improvable, while connection of wire bonding etc. is improved, since the opposite guard plate 11 is formed in the shape of a ctenidium.

[0047] Furthermore, in the gestalt of this operation, in order to paste up the cutting block 8 and the parallel guard plate 9 on the opposite guard plate 11 of the above-mentioned composition, gap parallelism does not pose a problem but it becomes easy to manufacture [of the compound-die magnetic head] it.

[0048] As mentioned above, this invention cannot be overemphasized by that it is not what is limited to this although explained using the compound—die magnetic head by which the three magnetic heads were put together and constituted from a gestalt of this operation. Moreover, with the gestalt of this operation, if the magnetic head which consists of a thin film magnetic—head substrate which has a thin—film—head element and an electrode drawer terminal at least, and an opposite protective—group board which protects this thin film magnetic—head substrate is included, it will be applied widely.

[0049]

[Effect of the Invention] The manufacture method of the compound—die magnetic head of this invention is starting the thin film magnetic—head substrate to which the opposite protective—group board formed in the shape of a ctenidium was joined for one chip. Since the magnetic—head section which will constitute the compound—die magnetic head is produced, cutting for exposing conventional grooving for a cutting criteria position marker check and a conventional electrode drawer terminal becomes unnecessary, and shortening of the production time by improvement of processing efficiency, improvement in productivity, and a cost cut are achieved.

[0050] Furthermore, the manufacture method of the compound-die magnetic head of this invention If the thin film magnetic-head substrate to which the opposite protective-group board was joined is cut, while an electrode drawer terminal top will be released Each cutting chip since [of an opposite guard plate] it leaves a lateral portion on the other hand and is cut Thus, when combining the compound-die thin film magnetic head which has the manufactured magnetic-head section, since [of an opposite guard plate] the lateral portion is left behind on the other hand, the area by the side of the adjoining magnetic-head section becomes large, and an assembly state will be stable. Therefore, while improvement in the assembly intensity of the compound-die magnetic head and assembly precision is achieved, it becomes possible to prevent making the hit by the magnetic-recording medium produce dispersion.

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DESCRIPTION OF DRAWINGS

[Brief Description of the Drawings]

[Drawing 1] It is drawing showing the manufacturing process of the compound—die magnetic head of the gestalt of the 1 operation to which this invention is applied, and is the perspective diagram showing the process which forms two or more thin film heads, and forms a thin-film substrate on a substrate.

[Drawing 2] It is drawing showing the manufacturing process of the above-mentioned compound-die magnetic head, and is the perspective diagram showing the cutting block which cuts a thin-film substrate and is formed.

[Drawing 3] It is drawing showing the manufacturing process of the above-mentioned compound-die magnetic head, and is the perspective diagram showing the state of pasting up a thin-film substrate, a parallel guard plate, and an opposite guard plate.

[Drawing 4] It is drawing showing the manufacturing process of the above-mentioned compound-die magnetic head, and is the perspective diagram showing the state of cutting an adhesion block for each chip.

[Drawing 5] It is drawing showing the manufacturing process of the above-mentioned compound-die magnetic head, and is the perspective diagram showing the state of cutting an adhesion block for each chip.

[Drawing 6] It is drawing showing the manufacturing process of the above-mentioned compound-die magnetic head, and is the perspective diagram showing the state where formed the magnetic-recording medium sliding surface in each chip, and the polish chip was produced. [Drawing 7] It is drawing showing the manufacturing process of the above-mentioned compound-die magnetic head, and is the perspective diagram showing the head chip which connects a printed wiring substrate to a polish chip, and is formed.

[Drawing 8] It is drawing showing the manufacturing process of the above-mentioned compound-die magnetic head, and is the perspective diagram showing the state where the compound-die magnetic head which has a thin film magnetic-head chip was assembled.

[Drawing 9] It is the ** type view showing the state where two or more head chips were pressurized in contact with the side orientation plate.

[Drawing 10] It is drawing showing the manufacturing process of the conventional compound—die magnetic head, and is the perspective diagram showing the process which forms two or more thin film magnetic heads, and forms a thin—film—head element substrate on a substrate.

[Drawing 11] It is drawing showing the manufacturing process of the conventional compound-die magnetic head, and is the perspective diagram showing the cutting block which cuts a thin-film-head element substrate and is formed.

[Drawing 12] It is drawing showing the manufacturing process of the conventional compound—die magnetic head, and is the perspective diagram showing the state of pasting up a thin-film-head element substrate, a parallel guard plate, and an opposite guard plate.

[Drawing 13] It is drawing showing the manufacturing process of the conventional compound-die magnetic head, and is the perspective diagram showing the state of cutting an adhesion block for each chip.

[Drawing 14] It is drawing showing the manufacturing process of the conventional compound—die magnetic head, and is the perspective diagram showing the state where the adhesion block was cut for each chip.

[Drawing 15] It is drawing showing the manufacturing process of the conventional compound—die magnetic head, and is the perspective diagram showing ****** which formed the magnetic—recording medium sliding surface in the chip, and produced the grinding chip.

[Drawing 16] It is drawing showing the manufacturing process of the above-mentioned compound-die magnetic head, and is the perspective diagram showing the head chip which connects a printed wiring substrate to a grinding chip, and is formed.

[Drawing 17] It is drawing showing the manufacturing process of the above-mentioned compound-die magnetic head, and is the perspective diagram showing the state where the compound-die magnetic head which has a thin film magnetic-head chip was assembled.

[Drawing 18] It is the ** type view showing the state where two or more head chips were pressurized in contact with the side orientation plate.

[Description of Notations]

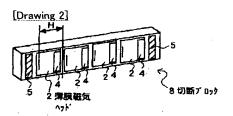
1, 1A, 1B, 1C Head chip 3 Thin-film-head element 4 Electrode drawer terminal 11 Opposite guard plate 11a On the other hand, an opposite guard plate is a side side. 11b Other side side side of an opposite guard plate 13 Concave opening 10 An adhesion block, 21 Compound-die magnetic head

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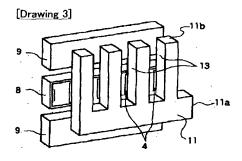
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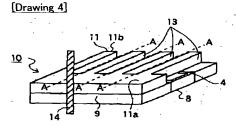
DRAWINGS

薄膜素子基板形成工程の斜視図



切断した薄膜条子基板の斜視図





[Drawing 5]

